

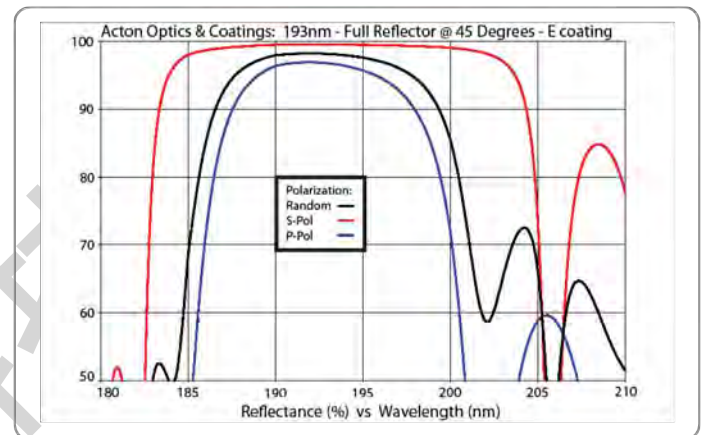
Application Specific

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193nm e-Design Approach High Fluence - Low Rep. Rate

Designed for applications requiring rep. rates of approximately 200 Hz, the e-design (ref: 193-FR45e) takes electrical field intensity (EFI) -correction to the next level by positioning and distributing EFI peaks within several layers, thus reducing the intensity within any single layer in the stack. This approach diminishes the effect of EFI-related damage resulting in increased laser damage resistance and longer coating lifetimes.



193nm XL-Design Approach Low Fluence - High Rep. Rate

The XL-design (ref: 193-XL45) combines hybrid structure with balanced stress for applications requiring rep. rates of 4-5 kHz. This minimizes the possibility of catastrophic damage due to micro-defects and thermal stress fractures, as well as prevents dehydration effects from high-repetition-rate operation. Reflectance of 96-97% at 193nm and phase shift can be optimized to customer's request. This robust UV coating passes MIL-SPEC adhesion, abrasion and humidity tests.

